

71. (new) The tantalum sputtering target of claim 69 having an average grain size of less than 50 microns at the target surface.

72. (new) The tantalum sputtering target of claim 69 having an average grain size of less than 25 microns at the target surface.

73. (new) A tantalum sputtering target comprising:

- (a) at least about 99.95 weight percent tantalum; and
- (b) a substantially uniform texture.

74. (new) An as-rolled tantalum target comprising:

- (a) at least about 99.95 weight percent tantalum; and
- (b) a substantially uniform {100} crystallographic orientation across a surface of said target.

75. (new) The as-rolled tantalum target of claim 74 having an average grain size of less than 50 microns at the target surface